Agency Contact:
Kelly Picasso
MCA
E-mail: kpicasso@mcapr.com

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GENISYS GMBH JOINS THE EBEAM INITIATIVE ROSTER TO ACCELERATE THE ADOPTION OF DESIGN FOR E-BEAM TECHNOLOGY

SAN JOSE, Calif., September 14, 2009—The eBeam Initiative, a forum dedicated to the education and promotion of a new design-to-manufacturing approach known as design for e-beam (DFEB), today announced that GenISys GmbH, a provider of e-beam software solutions, has joined its membership base. The Initiative provides a platform for GenISys to expand its collaboration and education efforts, while contributing to the Initiative's goal of increasing industry investment in the adoption of DFEB solutions.

GenISys' Layout BEAMER serves as a comprehensive data-preparation library that integrates proximity effect correction, writing strategy and resist effects—offering an advanced solution to achieve the best e-beam writing results on a wafer. The cooperation of equipment and software vendors, together with users, is important for the successful adoption of the Layout BEAMER software package. With more than 20 members across the ecosystem, the Initiative provides a platform for GenISys to expand its collaboration and education efforts globally.

"GenISys joining the eBeam Initiative came at an opportune time. The company is currently moving its advanced e-beam process modeling and correction technologies from R&D into production applications. At the 22-nm node and beyond, there is a serious need for these features in photomask and maskless lithography. We see the eBeam Initiative as a unique opportunity to expand our presence and recognition in the global market place," stated Ulrich Hofmann, founder and general manager of GenISys.

The eBeam Initiative welcomes other providers to help accelerate the adoption of DFEB. To find out more information on how you can join, please visit www.ebeam.org.

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About The eBeam Initiative
The eBeam Initiative provides a forum for educational and promotional activities regarding a new design-to-manufacturing approach, known as design for e-beam (DFEB). DFEB reduces mask costs for semiconductor devices by combining design, design software, manufacturing, manufacturing equipment and manufacturing software expertise. The goals of the Initiative are to reduce the barriers to adoption to enable more integrated circuit (IC) design starts and faster time-to-market while increasing the investment in DFEB throughout the semiconductor ecosystem. Members and advisors, which span the semiconductor ecosystem, include: Advantest, Alchip Technologies, Altos Design Automation, Cadence Design Systems, CEA/Leti, D2S, Dai Nippon Printing, Marty Deneroff from D. E. Shaw Research, e-Shuttle, Jack Harding from eSilicon Corporation, Fastrack Design, Fujitsu Microelectronics, GenISys GmbH, Magma Design Automation, Colin Harris from PMC-Sierra, Riko Radojcic from Qualcomm, STMicroelectronics, Tela Innovations, Toppan Printing, Virage Logic and Vistec Electron Beam Lithography Group. Membership is open to all companies and institutions throughout the electronics industry. To find out more, please visit www.ebeam.org.

About GenISys
Based in Munich, Germany, with offices in Tokyo, Japan and Santa Clara, California, GenISys combines deep technical expertise with high-caliber software engineering to develop flexible, high-performance software solutions. Addressing the market for e-beam direct write and optical lithography, GenISys products give researchers, manufacturers and system suppliers - in R&D and production - unparalleled efficiency, ease of use and optimal value. GenISys tools provide efficient processing and correction of large layout data, plus modeling and optimization of new micro-patterning technologies and microstructure fabrication processes. As a company focused on customer service, GenISys delivers fast, flexible support for the integration, customization and development of specialized functionality to meet unique customer needs. For more information on GenISys, visit the web site at www.genisys-gmbh.com.

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